



Power Electronics Reliability

2010 Update Conference – DOE ESS Program

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Mark A. Smith – Systems Readiness & Sustainment Technologies

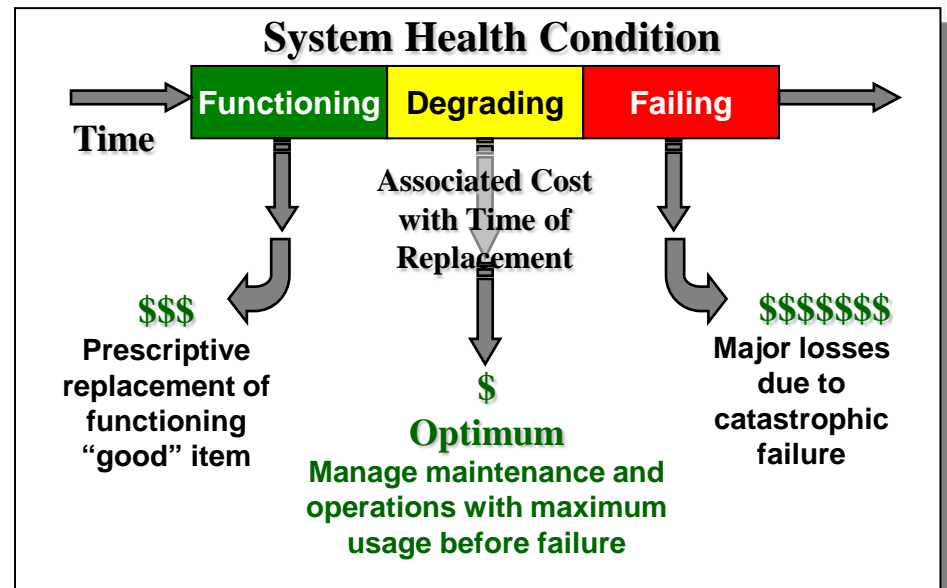
**Robert Kaplar, Matthew Marinella, Reinhard Brock, James Stanley,
and Michael King – Radiation Hard CMOS Technology**

Stan Atcitty – Energy Infrastructure and Distributed Energy Resources
Sandia National Laboratories

Thanks to Dr. Imre Gyuk for supporting this work.

Project Goals

- Use experiments and modeling to investigate and characterize stress-related failure modes of post-silicon power electronic (PE) devices such as silicon carbide (SiC) and gallium nitride (GaN) switches.
- Seek opportunities for condition monitoring (CM) and prognostics and health management (PHM) to further enhance the reliability of power electronics devices and equipment.
 - CM: detect anomalies and diagnose problems that require maintenance
 - PHM: track damage growth, predict time to failure, and manage subsequent maintenance and operations in such a way to optimize overall system utility against cost



Project Accomplishments

- **Developed relationships with several industrial and academic partners involved in post-silicon device work**
- **Obtained a number of samples of SiC devices for stress testing**
- **Modified experimental test set-ups to accommodate new devices and provide new stress conditions**
- **Performed stress testing on several devices to induce representative degradation signatures**
 - **Dielectric breakdown and flatband/threshold voltage shifts in SiC MOS capacitors**
 - **Bias temperature stress induced increase in SiC MOSFET on-state resistance**
 - **I-V curve shift in Schottky diode**
- **Demonstrated corresponding concepts for CM and PHM**

Materials and Devices/Tests

<u>Material</u>	<u>Formula</u>	<u>Band Gap</u>
Silicon	Si	1.11 V
Silicon Carbide	SiC	3.25 V*
Gallium Nitride	GaN	3.4 V*

*Depending on polytype

- **SiC vs. Si**
 - Higher breakdown field
 - Allows making lower on-state resistance devices
 - Higher temperature operation
 - Allows faster switching
 - More efficient grid equipment
 - Smaller footprint, higher density

- **Stress Tests**
 - SiC MOS capacitors
 - SiC MOSFETs
 - SiC Schottky Diodes
- **I-V Tests**
 - SiC JFETs
 - SiC Thyristors
- **Future Tests**
 - GaN HEMTs
 - Others (TBD)

Stress Tests

Stresses

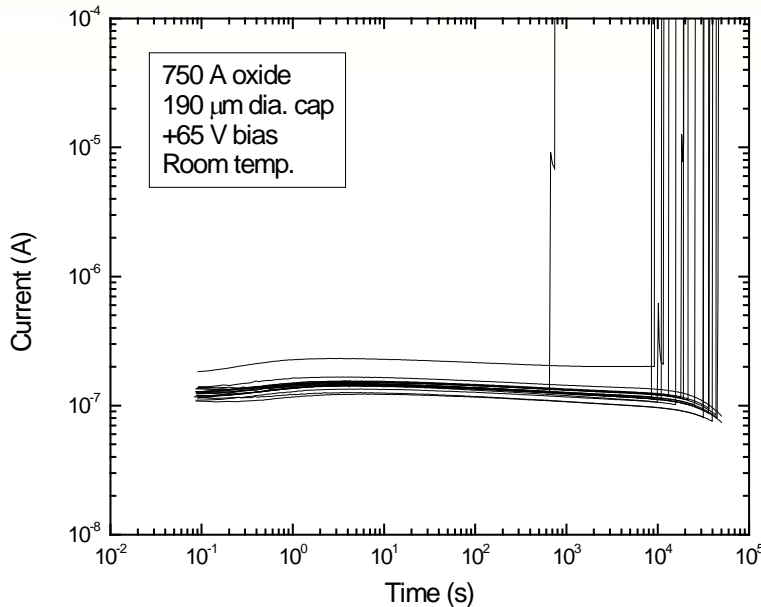
- **Voltage**
- **Current**
- **Elevated Temperature**
- **Bias Temperature Stress (BTS)**
- **Other Combinations**

Effects

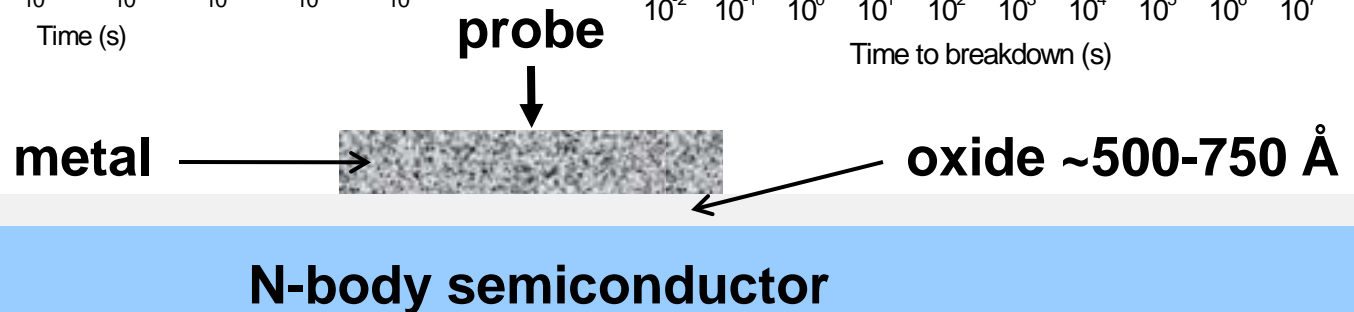
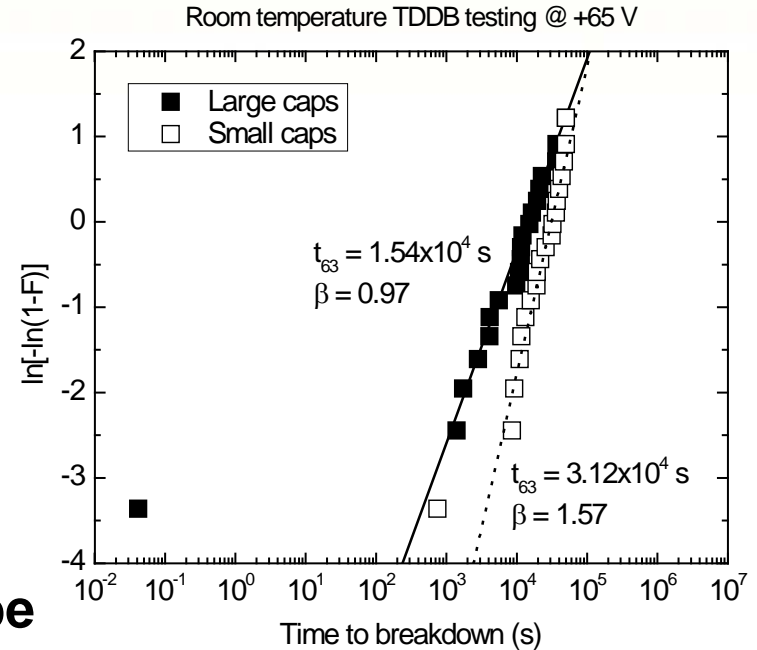
- **TDDDB (Time-Dependent Dielectric Breakdown)**
- **HCI (Hot Carrier Injection on smaller devices)**
- **NBTI (Negative-Bias Temperature Instability)**
- **Flatband/threshold shift (charge injection from BTS)**
- **Snapback**
- **Reverse Bias Breakdown**
- **Others (device dependent)**

SiC MOS capacitors (TDDB)

Current vs. Time

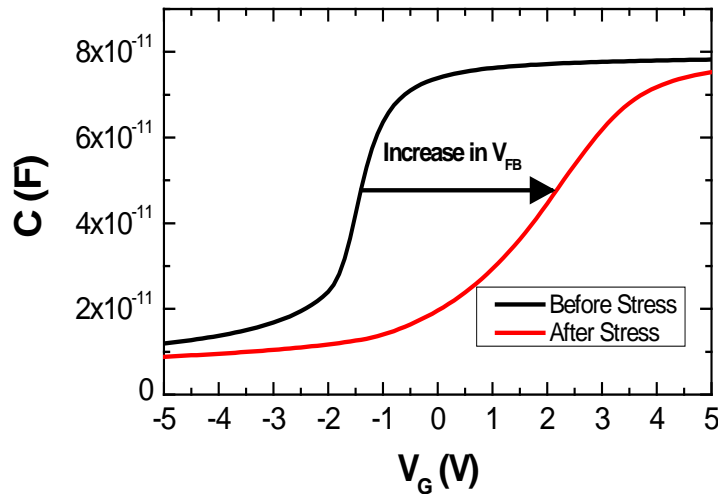


Weibull Fit

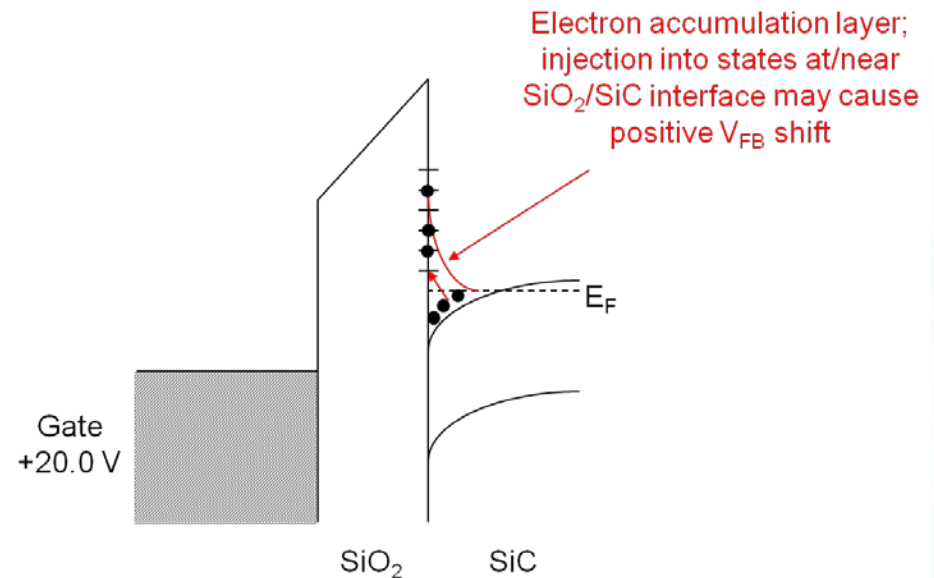


SiC MOS Capacitors (BTS tests)

Capacitance-voltage (C-V) curves before and after temperature stress

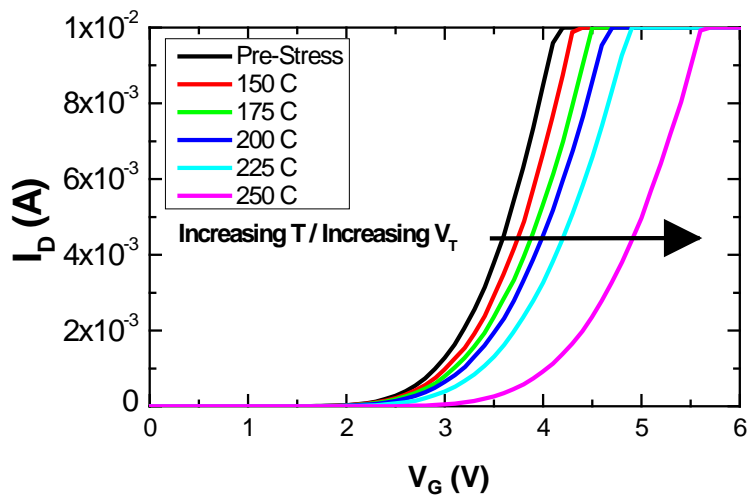


Negative charge injection into traps at/near the oxide semiconductor interface

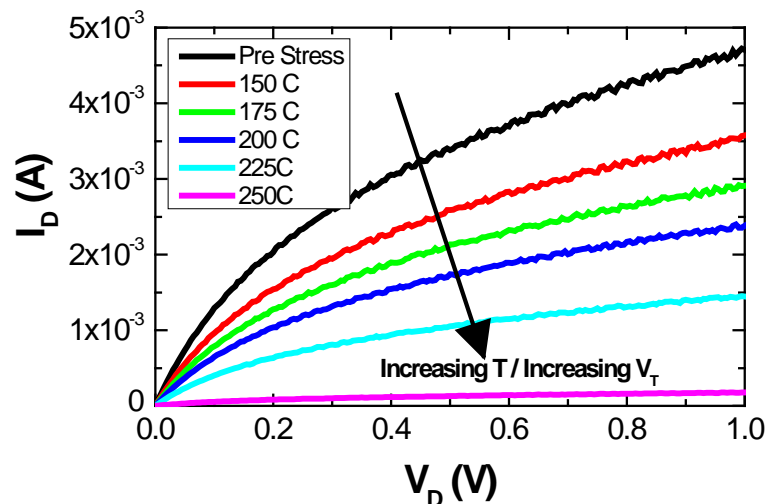


SiC MOSFET (BTS tests)

Drain Current vs. Gate Voltage ($V_D = 1$ V)



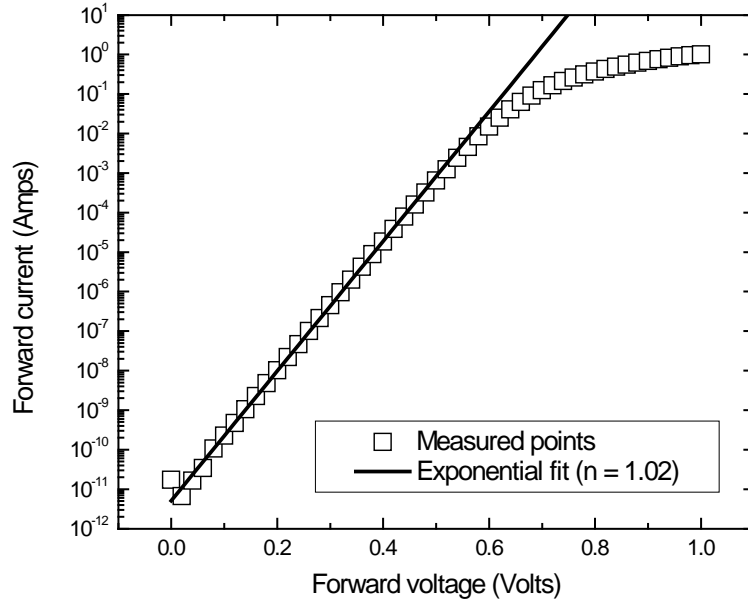
Drain Current vs. Drain Voltage ($V_G = 3.5$ V)



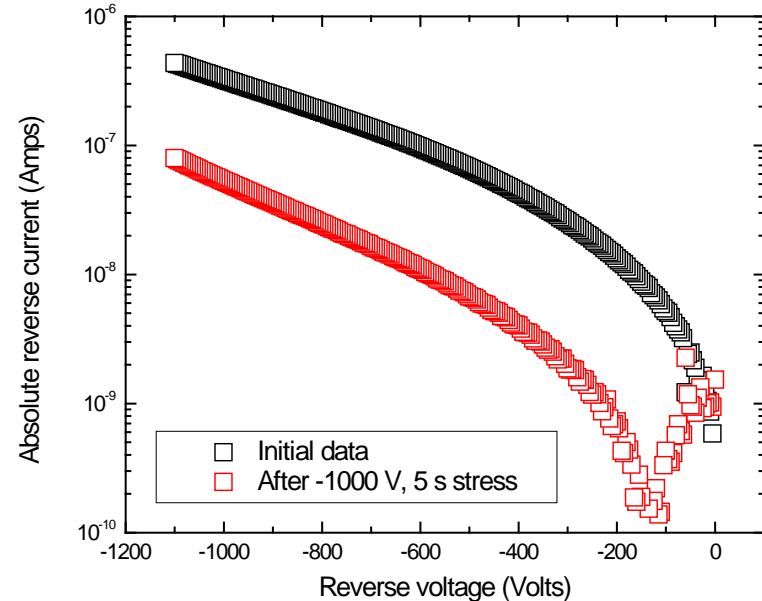
Bias temperature stress induces higher on-state resistance.

SiC Schottky Diodes

Forward I-V Curve

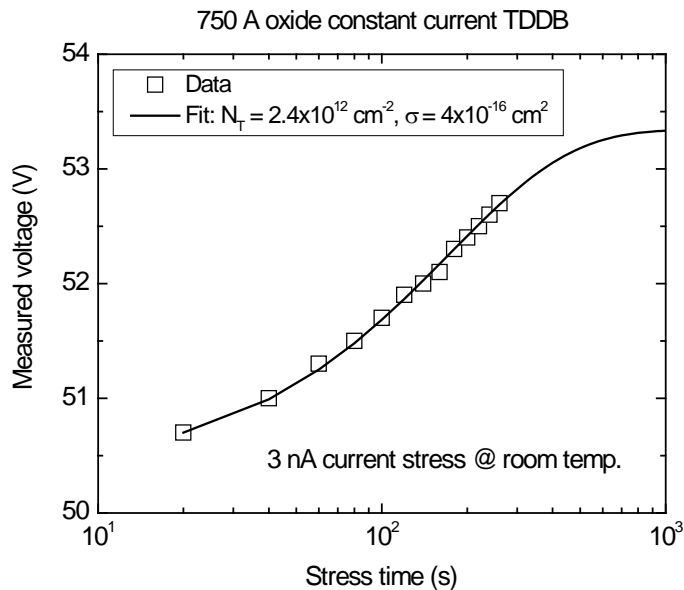


Effect of Voltage Stress on Reverse I-V Curve

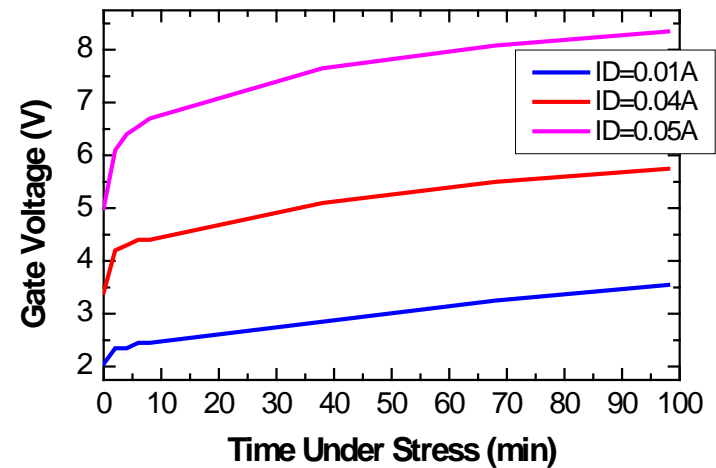


CM/PHM Concepts

Charge Accumulation in SiC MOS Capacitor



Voltage Threshold Shifts in SiC MOSFET



Conclusions

- **Benefits of CM/PHM**
 - **Operate power conversion systems in ways that will preclude predicted failures**
 - **Reduce unscheduled downtime and thereby reduce costs**
 - **Pioneering reliability in SiC and GaN**
- **Future Work**
 - **Higher stresses**
 - **Test simple sensors vs. laboratory instruments**
 - **Once failure progression is understood, could design devices that degrade gracefully to facilitate PHM**
 - **Emerging field: publications in basic physics**



Questions?